



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Patricia B. Smith et al. Art Unit: 2823
Serial No.: 09/199/829 Examiner: Eaton, K.
Filed: 11/25/98 Docket No.: TI-25250
For: Hydrogen Plasma Photoresist Strip and Polymeric Residue Cleanup
Process for Oxygen-Sensitive Materials

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10/18/00

INFORMATION DISCLOSURE STATEMENT

September 28, 2000

Assistant Commissioner for Patents
Washington, DC 20231

Dear Sir:

Please make the references listed on the enclosed PTO-1449 of record under 37 C.F.R. 1.56, 1.97, and 1.98 in the patent application identified above. Copies of the listed references are enclosed.

Respectfully submitted,

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